

Taher E Kagalwala

List of Publications by Year in descending order

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Version: 2024-02-01

16
papers

70
citations

1684188
5
h-index

1872680
6
g-index

16
all docs

16
docs citations

16
times ranked

48
citing authors

#	ARTICLE	IF	CITATIONS
1	Improving Metrology Fleet KPIs for Advanced Foundry Manufacturing. , 2019, , .		1
2	Characterization of Overlay and Tilt in Advanced Technology Nodes using Scatterometry. , 2019, , .		2
3	Nonconventional applications of Mueller matrix-based scatterometry for advanced technology nodes. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2018, 17, 1.	0.9	18
4	Implementation of machine learning for high-volume manufacturing metrology challenges (Conference Presentation). , 2018, , .		2
5	Advanced applications of scatterometry based optical metrology. Proceedings of SPIE, 2017, , .	0.8	6
6	Complex metrology on 3D structures using multi-channel OCD. Proceedings of SPIE, 2017, , .	0.8	0
7	Optical metrology strategies for inline 7nm CMOS logic product control. , 2017, , .		0
8	High throughput and dense sampling metrology for process control. Proceedings of SPIE, 2017, , .	0.8	2
9	SAQP pitch walk metrology using single target metrology. , 2017, , .		1
10	Scatterometry-based metrology for SAQP pitch walking using virtual reference. , 2016, , .		1
11	A Combined Gas Cluster Ion Beam (GCIB) and Chemical-Mechanical Polish (CMP) Planarization Scheme for Tungsten Replacement Metal Gate (W-RMG). ECS Journal of Solid State Science and Technology, 2016, 5, P404-P408.	1.8	8
12	Measuring self-aligned quadruple patterning pitch walking with scatterometry-based metrology utilizing virtual reference. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2016, 15, 044004.	0.9	9
13	Integrated metrology's role in Gas Cluster Ion Beam etch. , 2015, , .		3
14	Leveraging advanced data analytics, machine learning, and metrology models to enable critical dimension metrology solutions for advanced integrated circuit nodes. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2014, 13, 041415.	0.9	17
15	MBIR characterization of Photosensitive Polyimide in high volume manufacturing. , 2014, , .		0
16	Leveraging data analytics, patterning simulations and metrology models to enhance CD metrology accuracy for advanced IC nodes. Proceedings of SPIE, 2014, , .	0.8	0